

X-Ray Microscopy for Interconnect Characterization

Frontiers of Characterization and Metrology for Nanoelectronics

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President, CTO, Founder

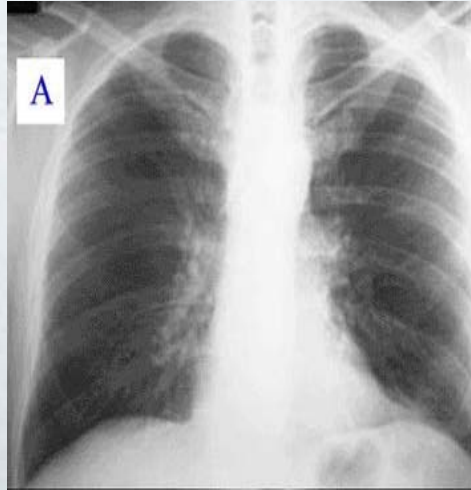
,May 13, 2009



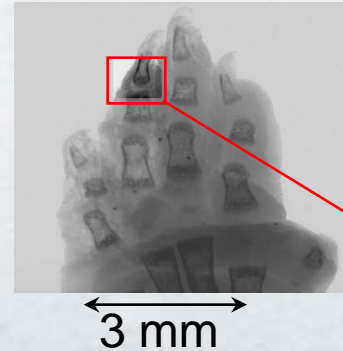
X-ray Imaging Advantages



1896,
Röntgen

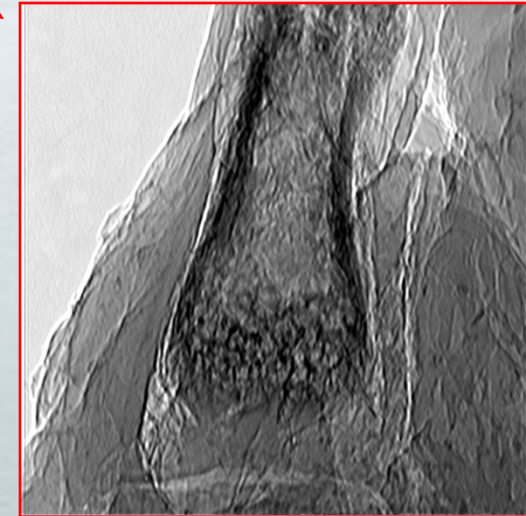


Chest x-ray



newborn mouse
paw

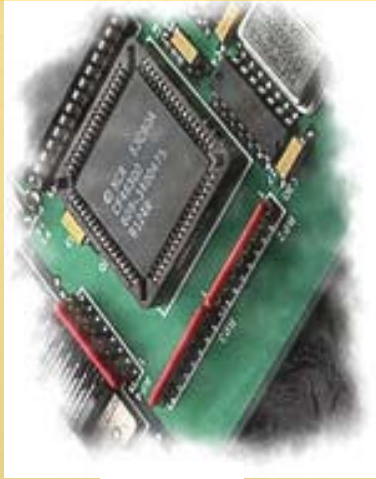
microfocus x-ray
sources and high
resolution CCDs



- **Nondestructive and 3D**
- Resolution is Not diffraction limited (8 keV x-rays = 1.5Å wavelength!)
- No need for conductive coating (Photons don't have charge)
- Minimal and no sample preparation
- No vacuum required. Fully hydrated thick samples (hard x-rays)

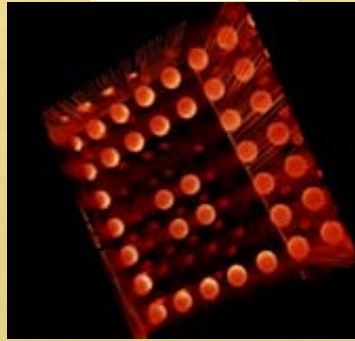
Multi-Length Scale Capabilities : Semiconductor

MicroXCT



Board

Flip Chip



20 μm

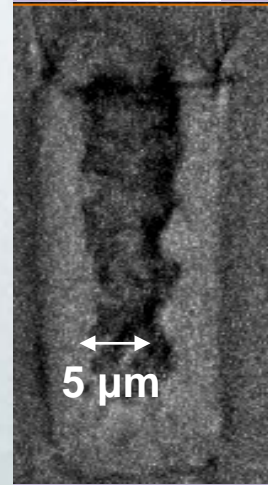
1 μm

Applications::

- Advanced package development
- Through silicon vias (>20 μm)
- Failure and reliability analysis
 - Solder ball crack
 - C4 bump crack

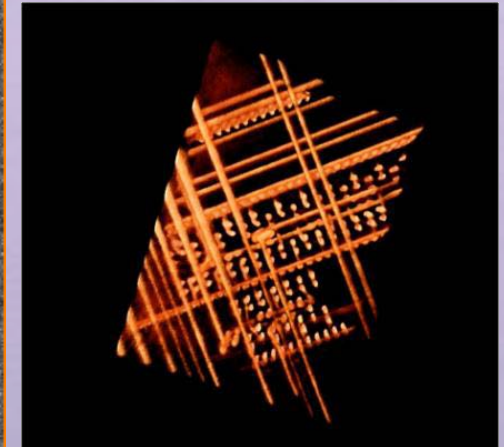
nanoXCT

TSV



5 μm

Interconnect



150 nm

50 nm

Applications::

- Advanced interconnect development
- Through silicon vias (<20 μm)
- Failure and reliability analysis
 - Open & short
 - Static discharge

Nanoscience needs nanoimaging (Seeing is believing)

- ❑ Nondestructive
- ❑ High resolution
- ❑ Element specific
- ❑ Magnetism
- ❑ Probing chemical and electron states

X-ray nano-imaging

Nondestructive
3D imaging at
Nanometer scale

IC
Manufacturing

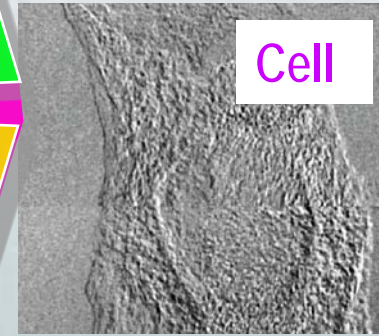
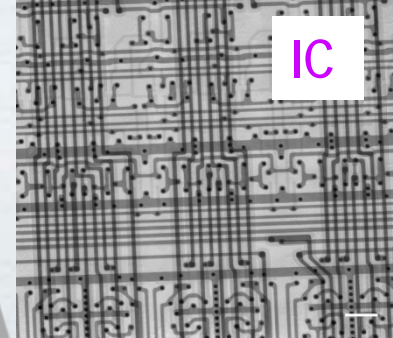
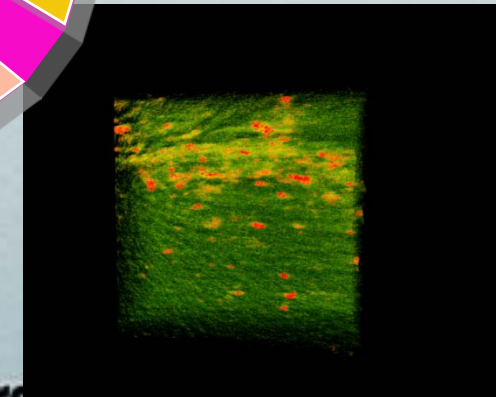
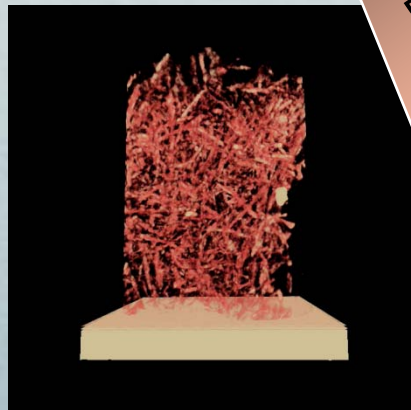
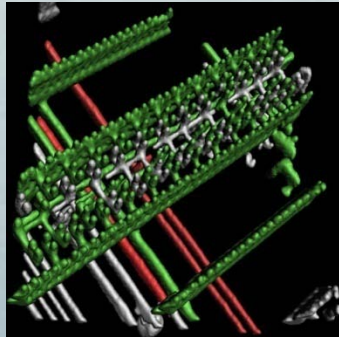
Biotechnology

Nanotechnology

R&D Centers

IC

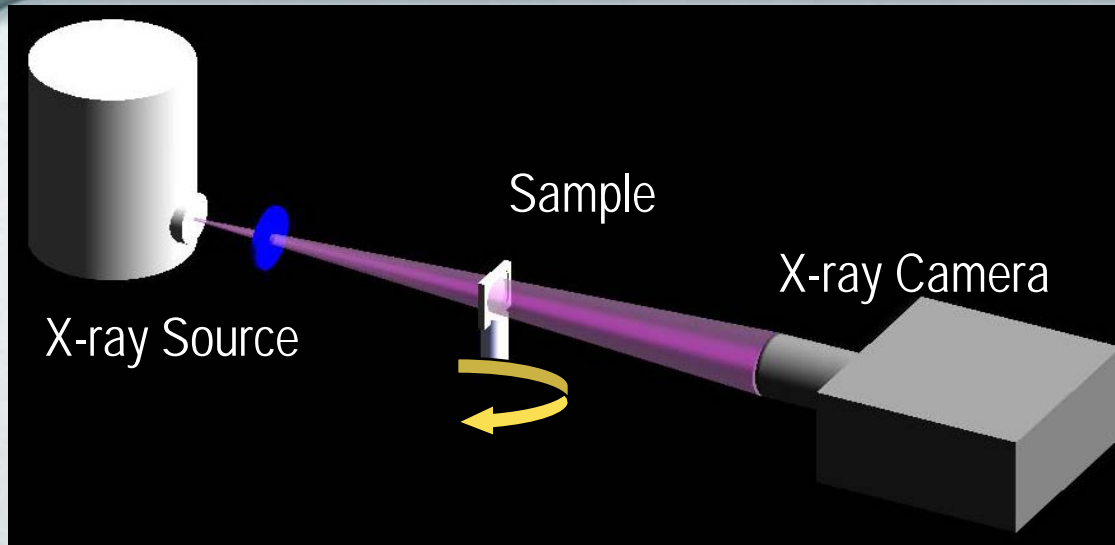
Cell



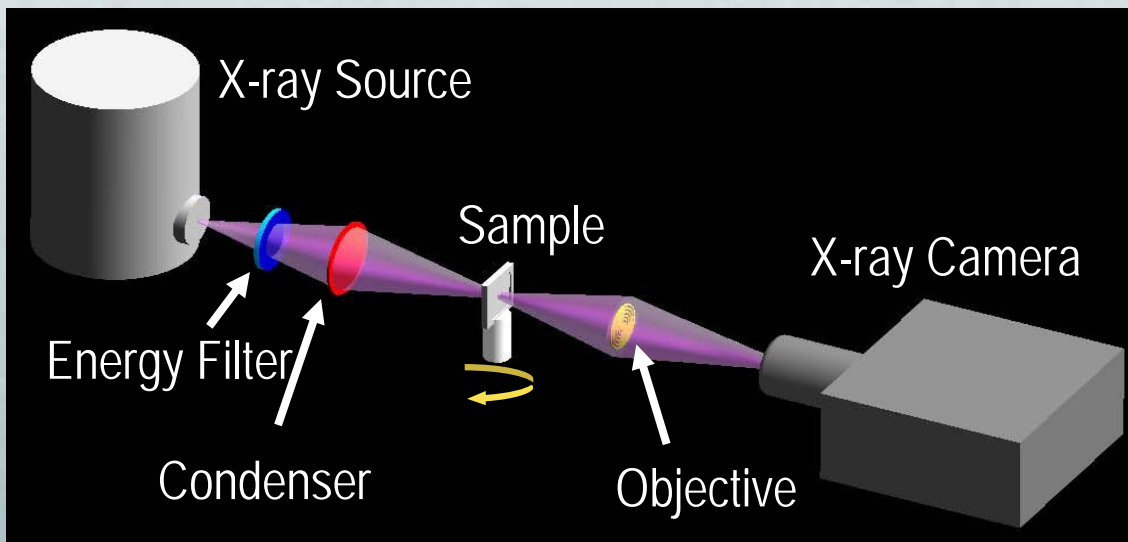
Competitive Analysis: Other Imaging Tools

	X ray	Optical	SEM	(S)TEM
Spatial resolution	30 nm	200-300 nm	1-10 nm	0.1 nm
Contrast Mechanism	Absorption, Phase Contrast	Transmission, Reflectivity, Refractive Index, Labels	Secondary El., Backscattered El., EDS/WED	Electron Density, spectroscopy
Probing depth	~100-1000 μm	Optically transparent only	< 10 nm typical	<200 nm
Sample preparation	Minimal	Minimal	Medium	Extensive
3D imaging	Yes	Yes	No, needs FIB or other preparation	Yes Very small vol.
3D image volume	10-60 μm up to 50mm	> 50 μm	No, needs FIB or other preparation	< 0.5 μm
Material class	All	Optically Transparent	Conductive path required > Charging	Conductive path required > Charging
Vacuum requirement	No	No	Yes	Yes

Full Field X-ray Imaging Methods

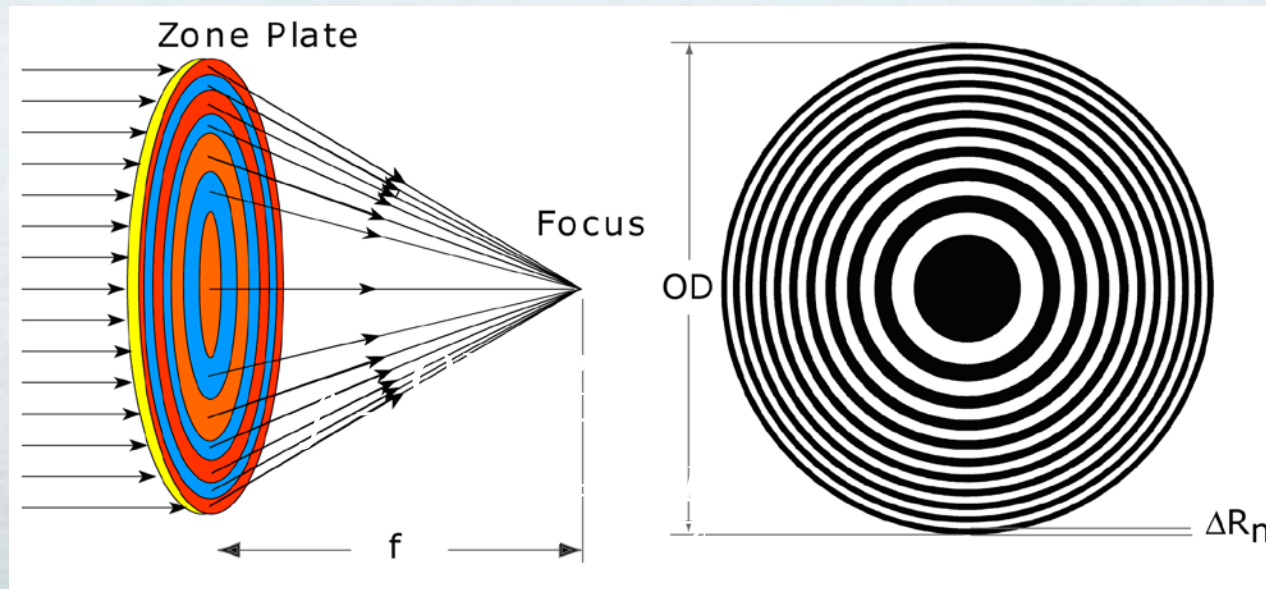


Point Projection Imaging



Lens Based Imaging

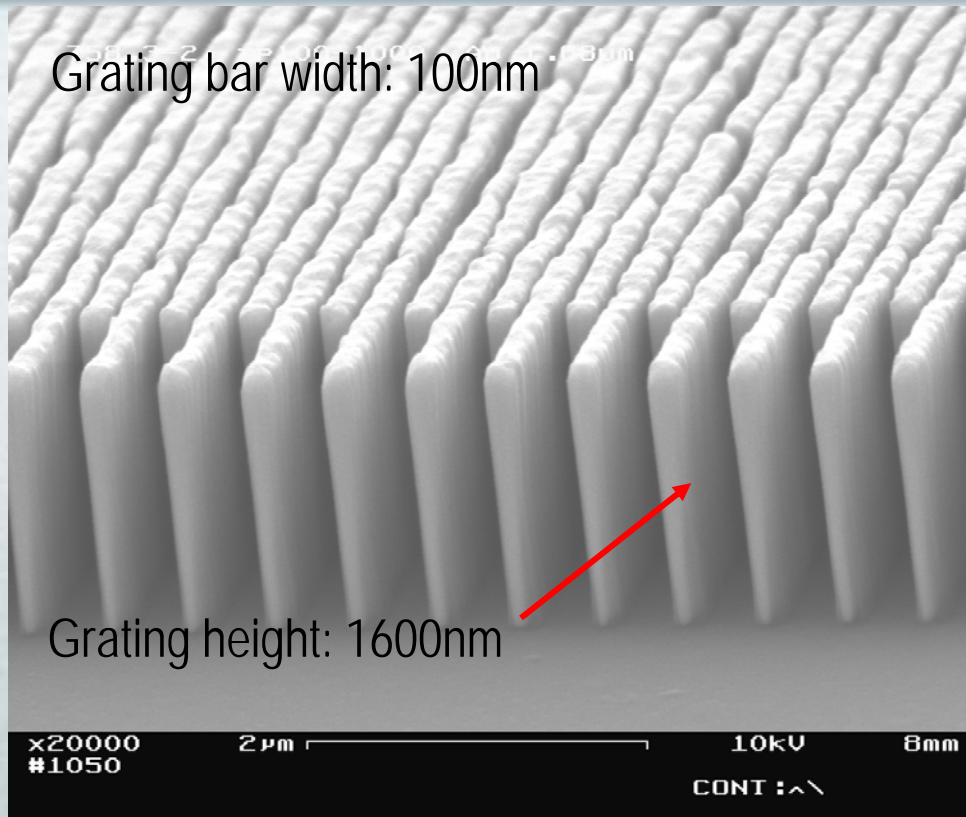
Highest Resolution X-ray Optics: Zone Plate Lenses



- ❑ Zone plates are diffractive x-ray lenses with high resolution (<30nm)
- ❑ Circular grating with radially varying pitch focuses x-rays to a point
- ❑ Focal length with **strong wavelength dependence**:

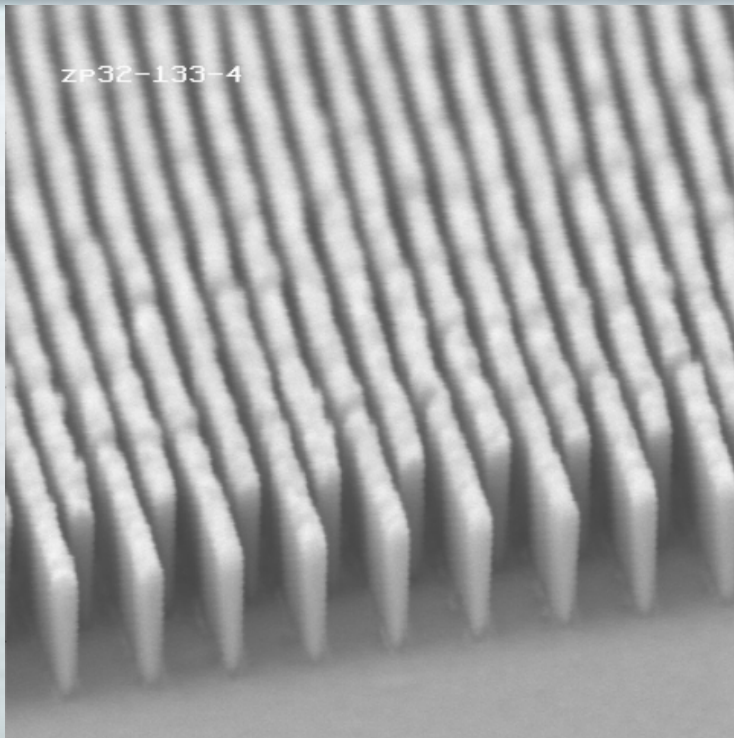
- ❑ Zone plates enable wavelength specific imaging

Scanning Electron Micrographs of Gold Zone Plates

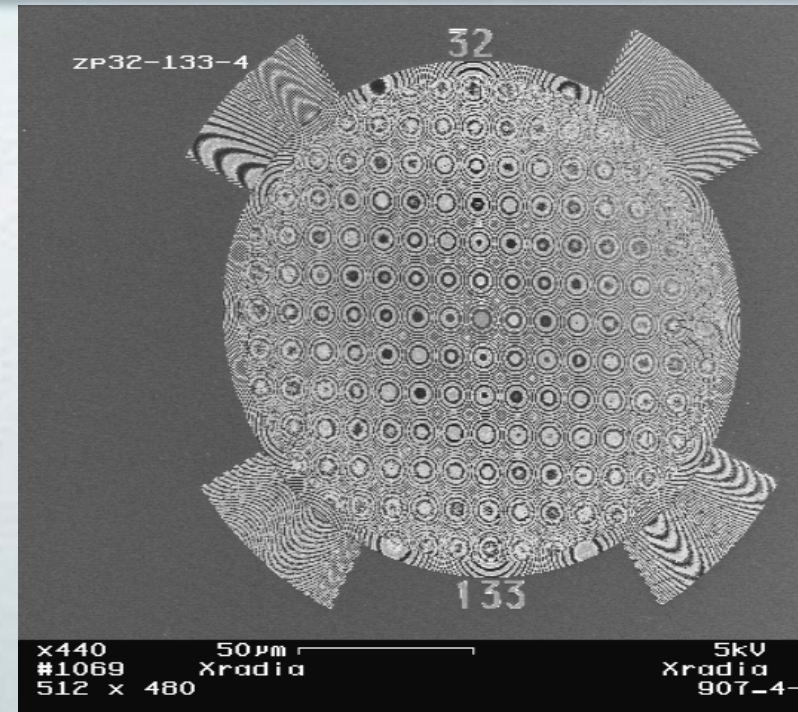


- ❑ Zone plates are fabricated out of high-Z (typically gold) material using electron beam lithography, reactive ion etching and electroplating
- ❑ Focusing efficiencies 10-30% currently achievable

Recent Fabrication Highlights



Cross section view of control structure
450nm zone height
32nm structure width



32nm zone width, 133µm diameter
450nm thickness

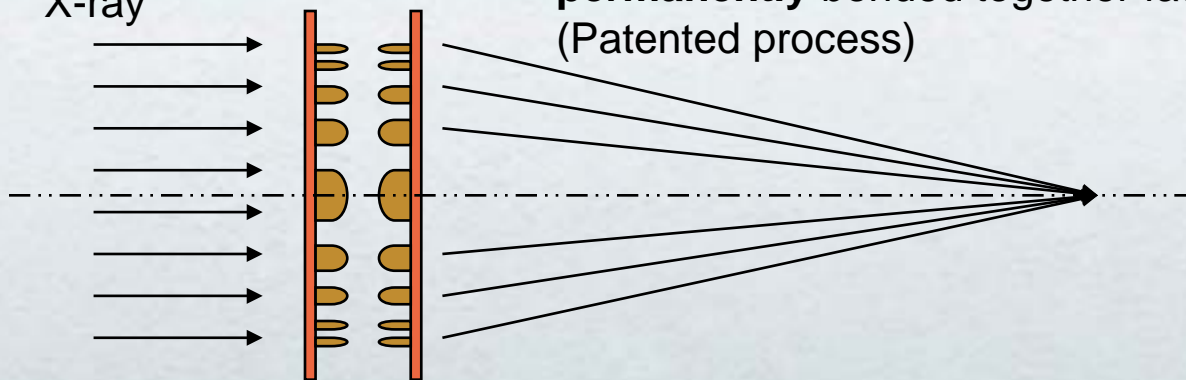
- 32nm gold zone plates, 450nm thick fabricated for CNM nanoprobe project (Xradia under contract), AR=14
- 24nm gold zone plate, 300nm fabricated recently, aligned to produce an effective thickness of 600 nm

High-resolution, High-efficiency Zone Plates



Monochromatic X-ray

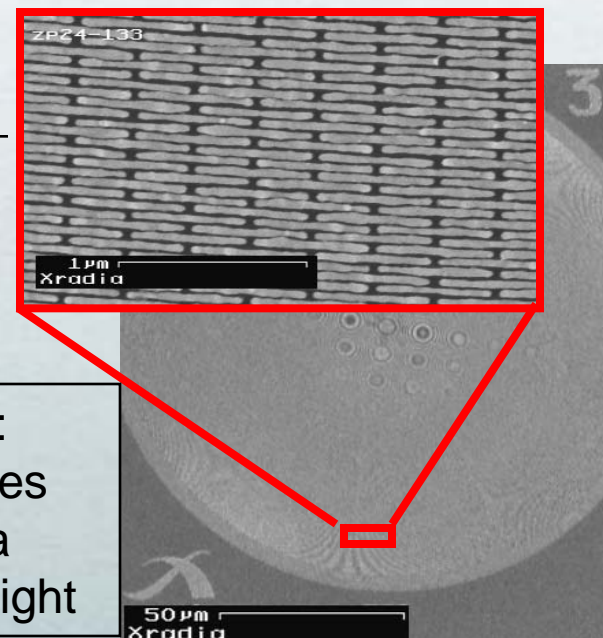
Two zone plates are aligned and **permanently** bonded together face-to-face. (Patented process)



Two zone plates act effectively as one diffractive element if aligned precisely laterally and in very close proximity (within depth of focus of lens)

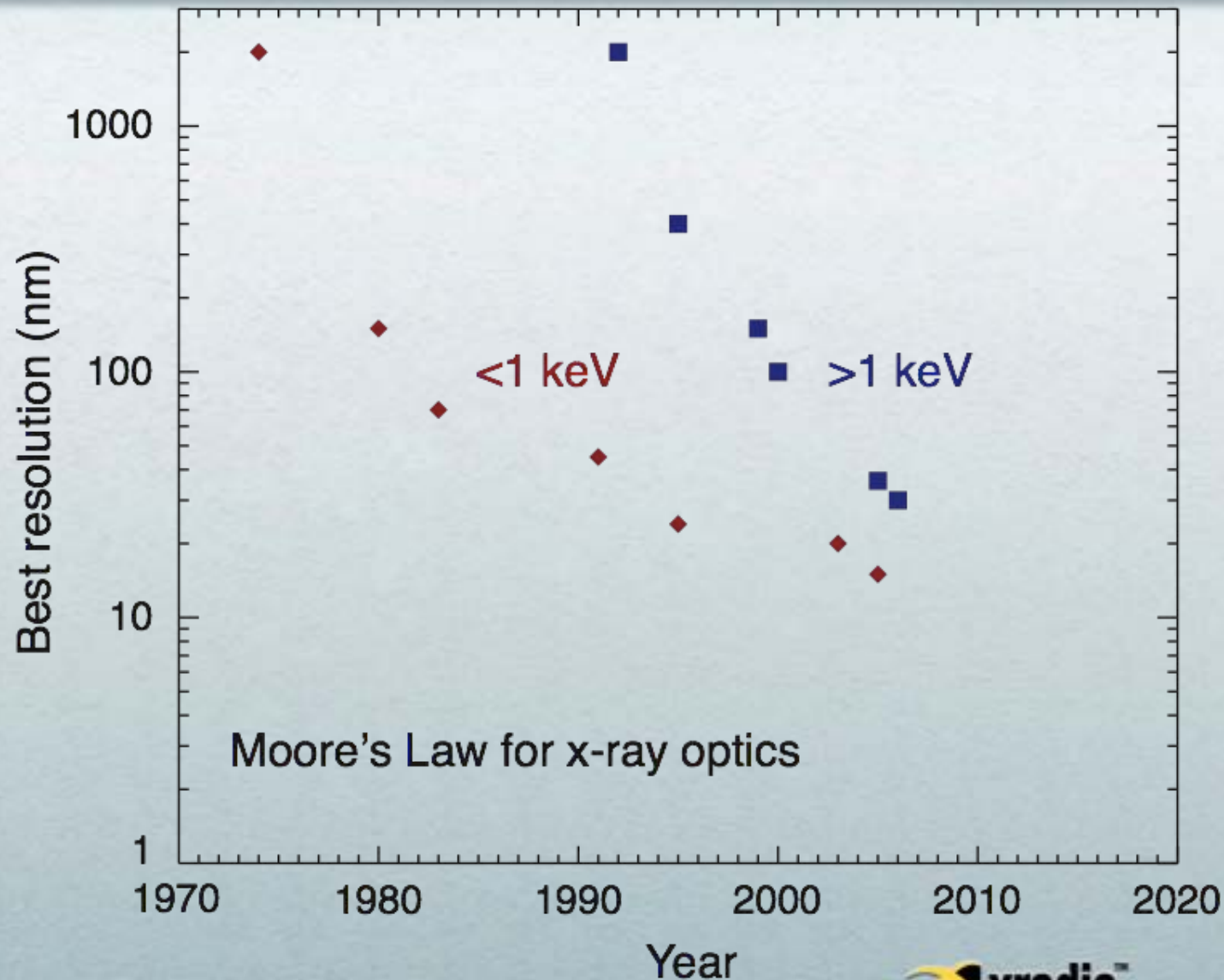
- High-resolution zone plates usually low efficiency
- Alignment to increase zone height increases efficiency
- 24nm zone width zone plates with combined 600nm height in use at ANL ID-26 nanoprobe.

Single ZP:
24nm zones
133um dia
300nm height



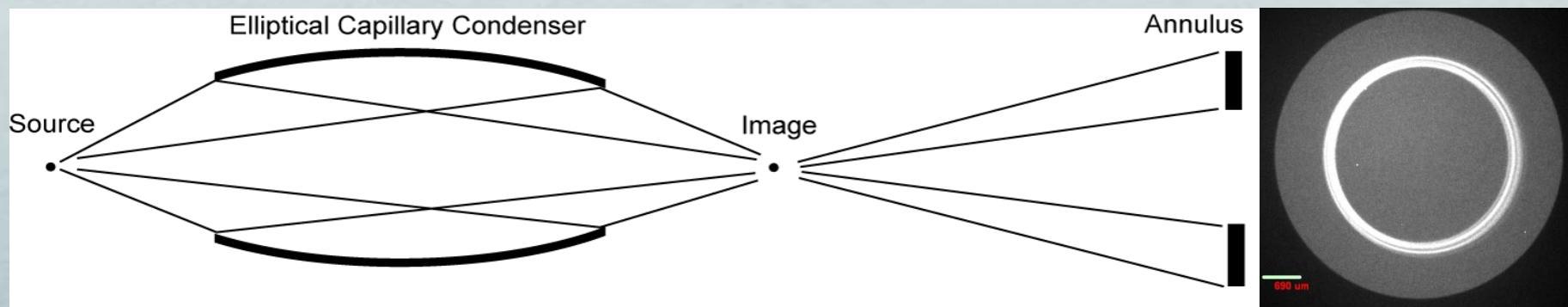
Y. Feng, et al., *Journal of vacuum science and technology B*, 25 (6), 2008

X-ray optics: best resolution



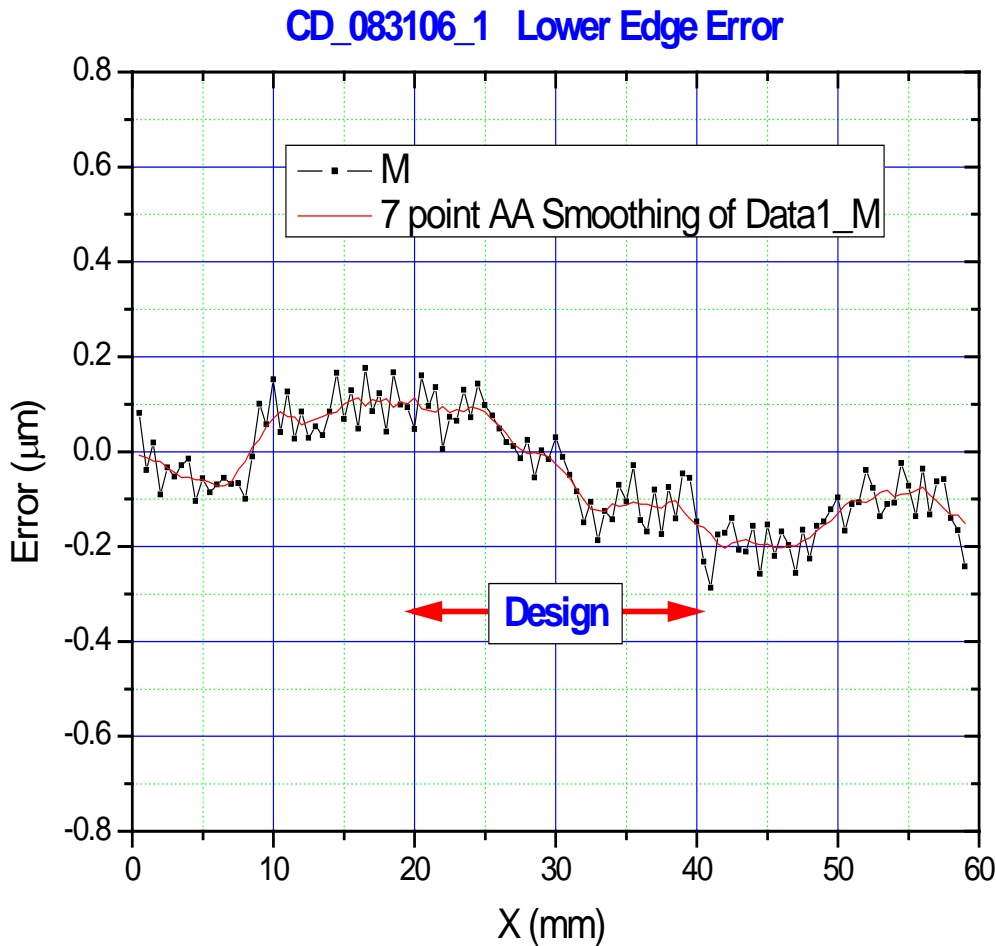
Elliptically Shaped Mono-Capillary Focusing Optics

- ❑ <3 μ m focusing achieved (using full aperture)
- ❑ Axially symmetric optic with high reflection efficiency (>90% for most energies), limited by critical angle
- ❑ Specific designs to match the numerical aperture (illumination angles) for zone plate objectives in full-field x-ray microscope



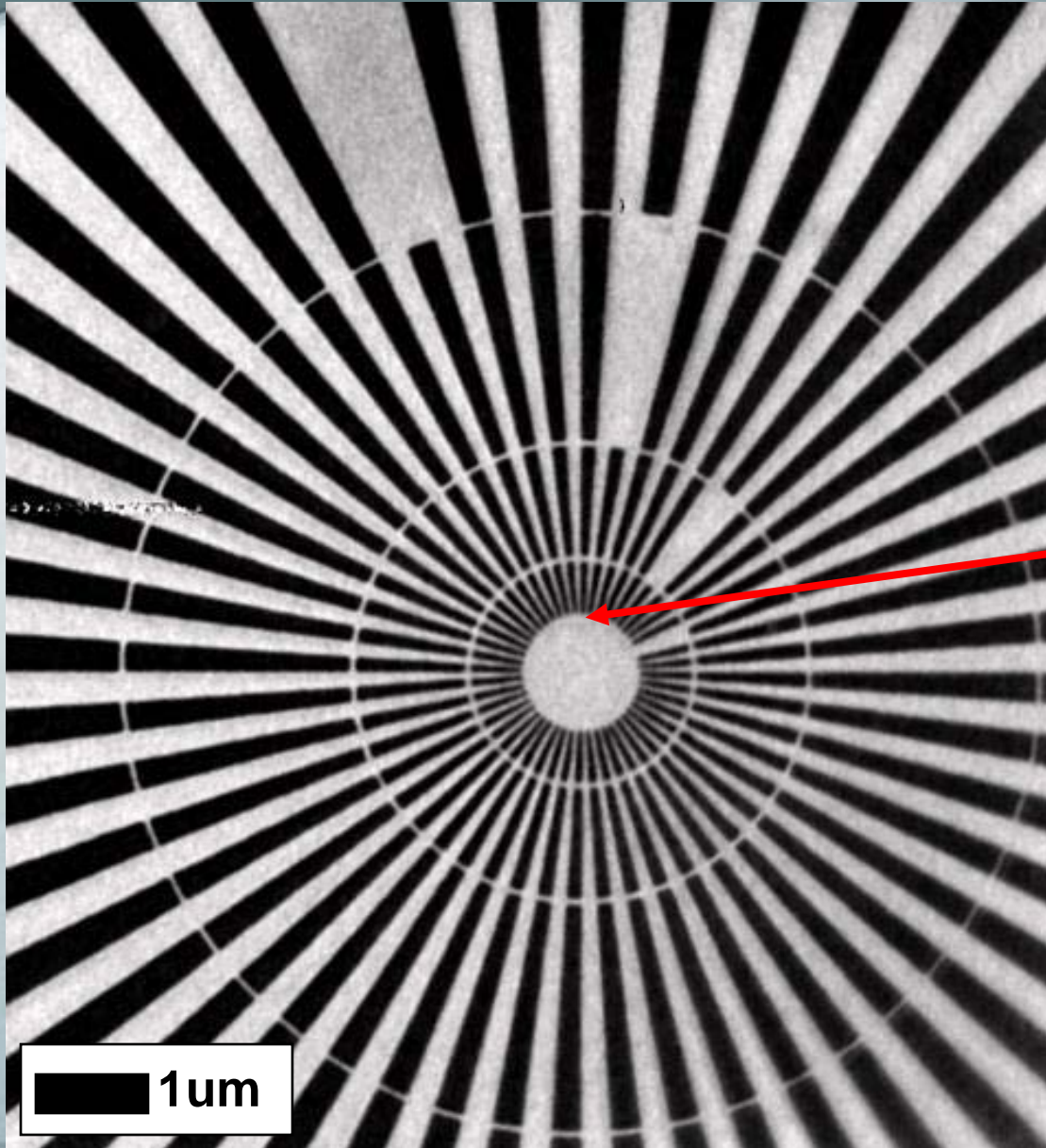
Mono-capillaries Quality Measurements

Deviation from perfect elliptical shape of 300um diameter capillary (μm)



- Elliptical figure shape is controllable to few 100nm
- Optical metrology system developed by Xradia

Sub-50 nm Laboratory X-ray Image

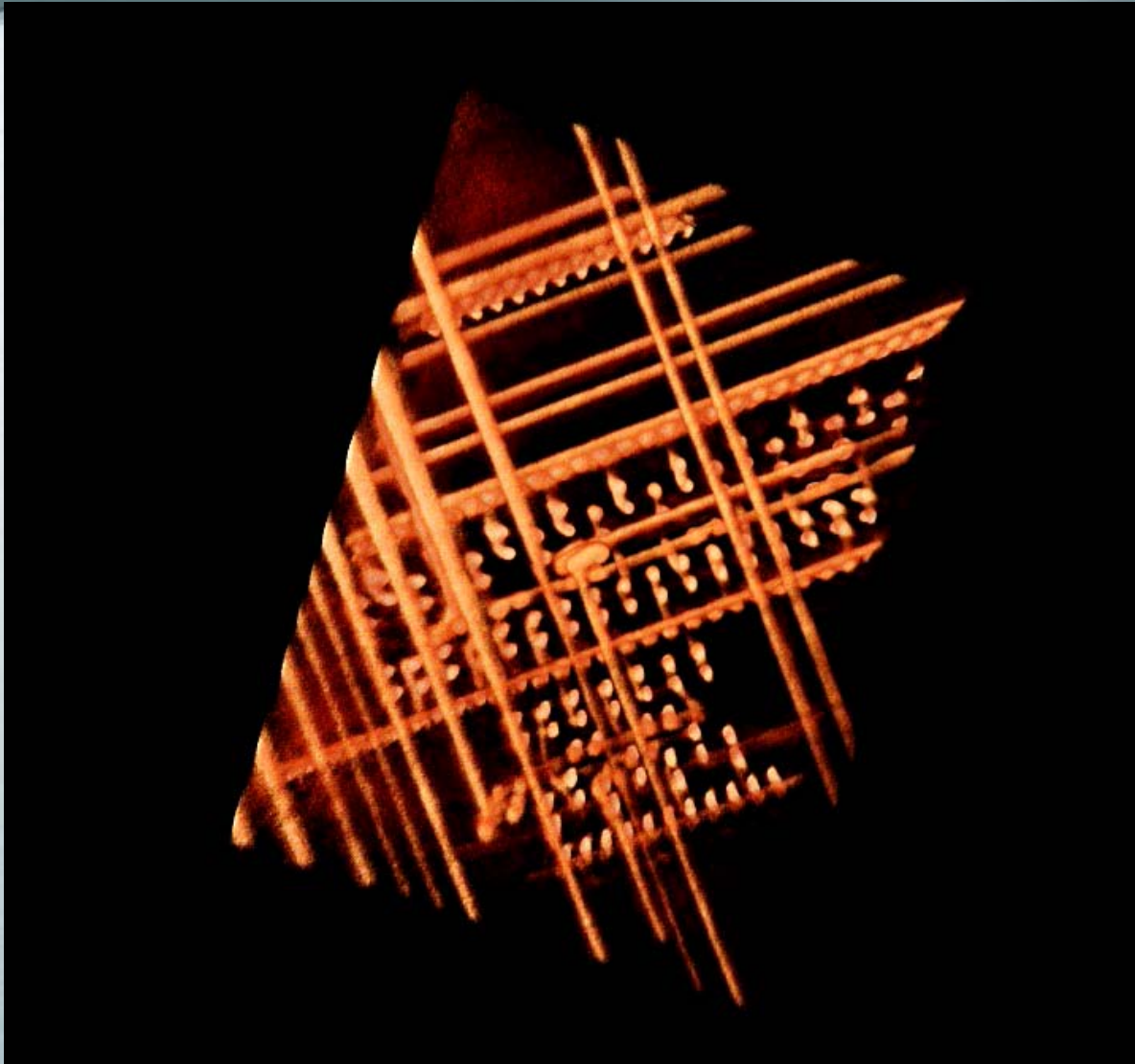


- Xradia nanoXCT 5-50
- Cr (5.4kV)
 - 35nm zone plate optic

Xradia Resolution & Calibration Test Pattern X50-30

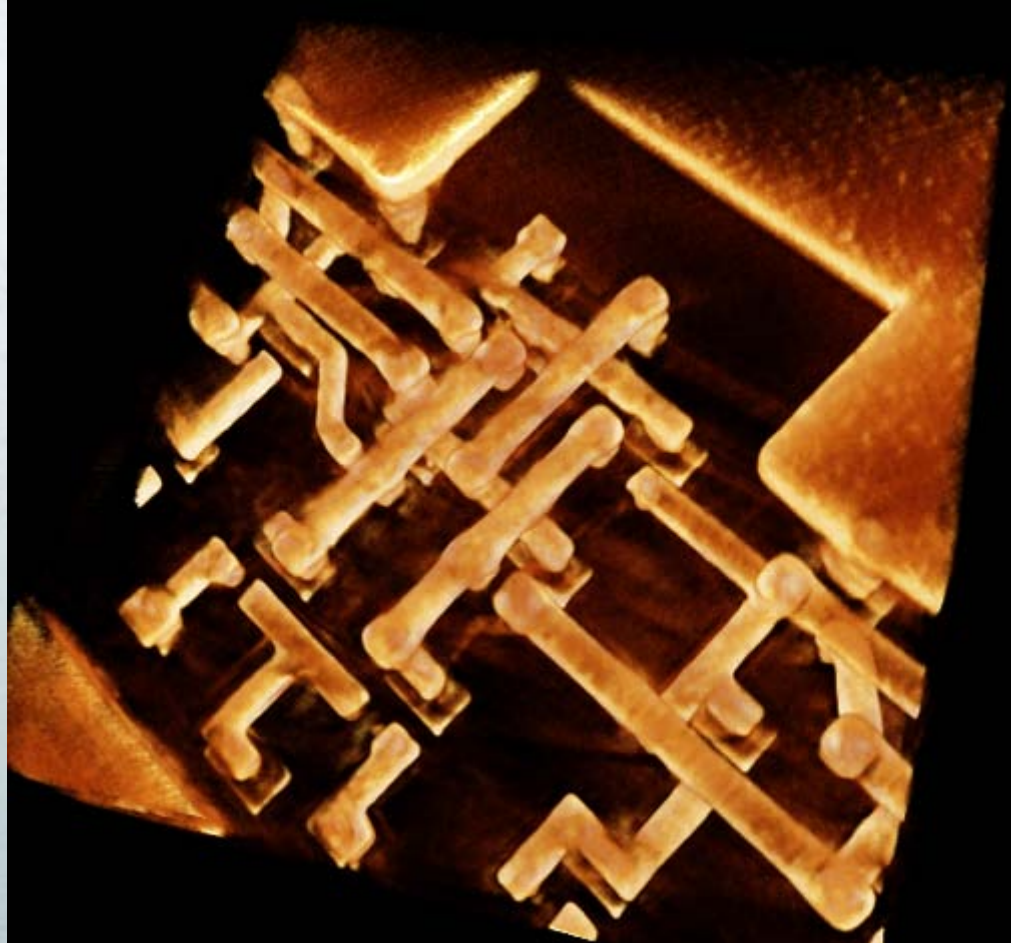
- 50 nm minimum line
- 100 nm mini. period
- 150 nm thick Au

Volume Rendering of a 90nm Technology Node IC

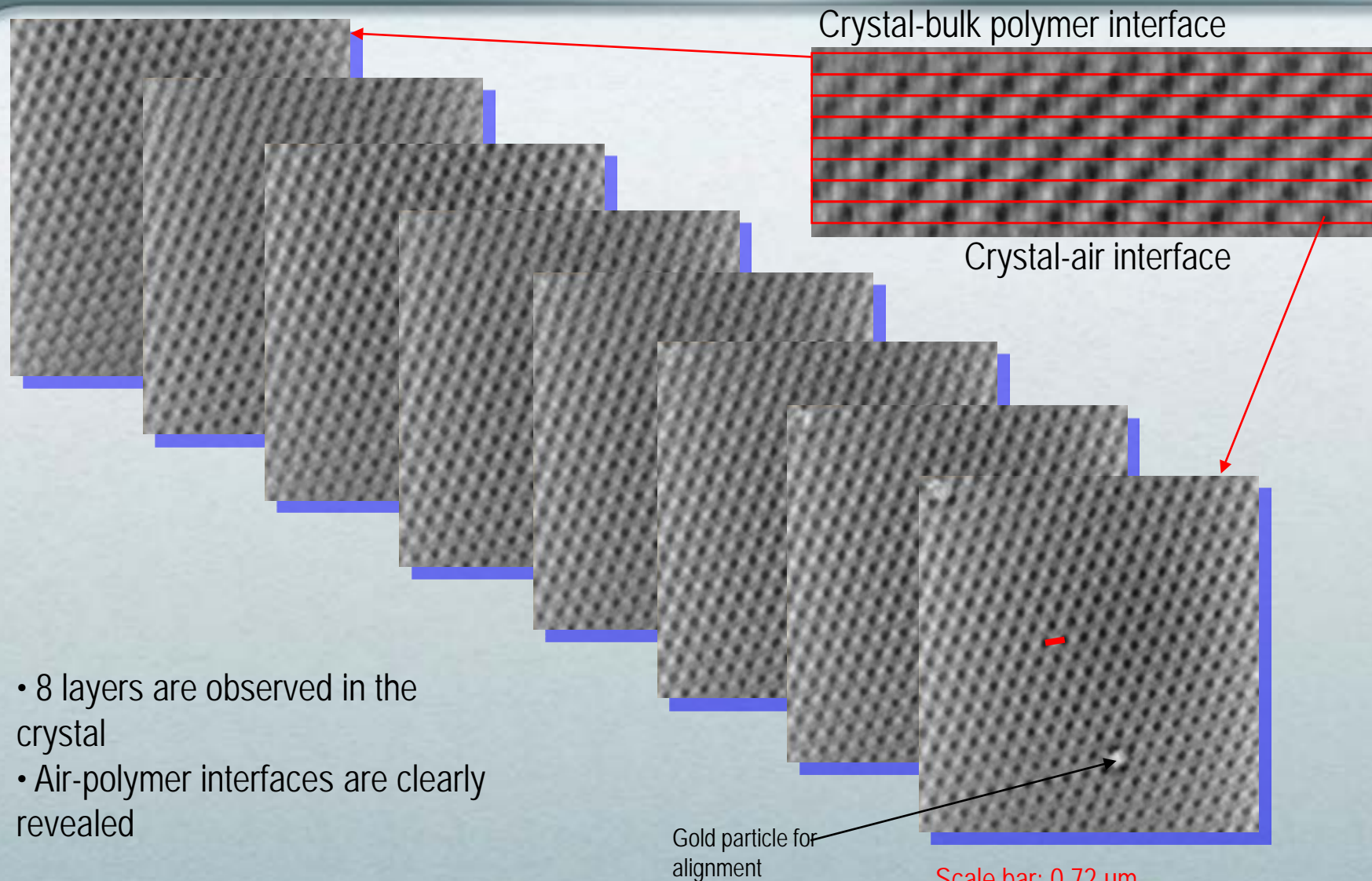


20min exposure at
SSRL synchrotron

X-ray Tomography of IC Device Up to 100 μm Thick



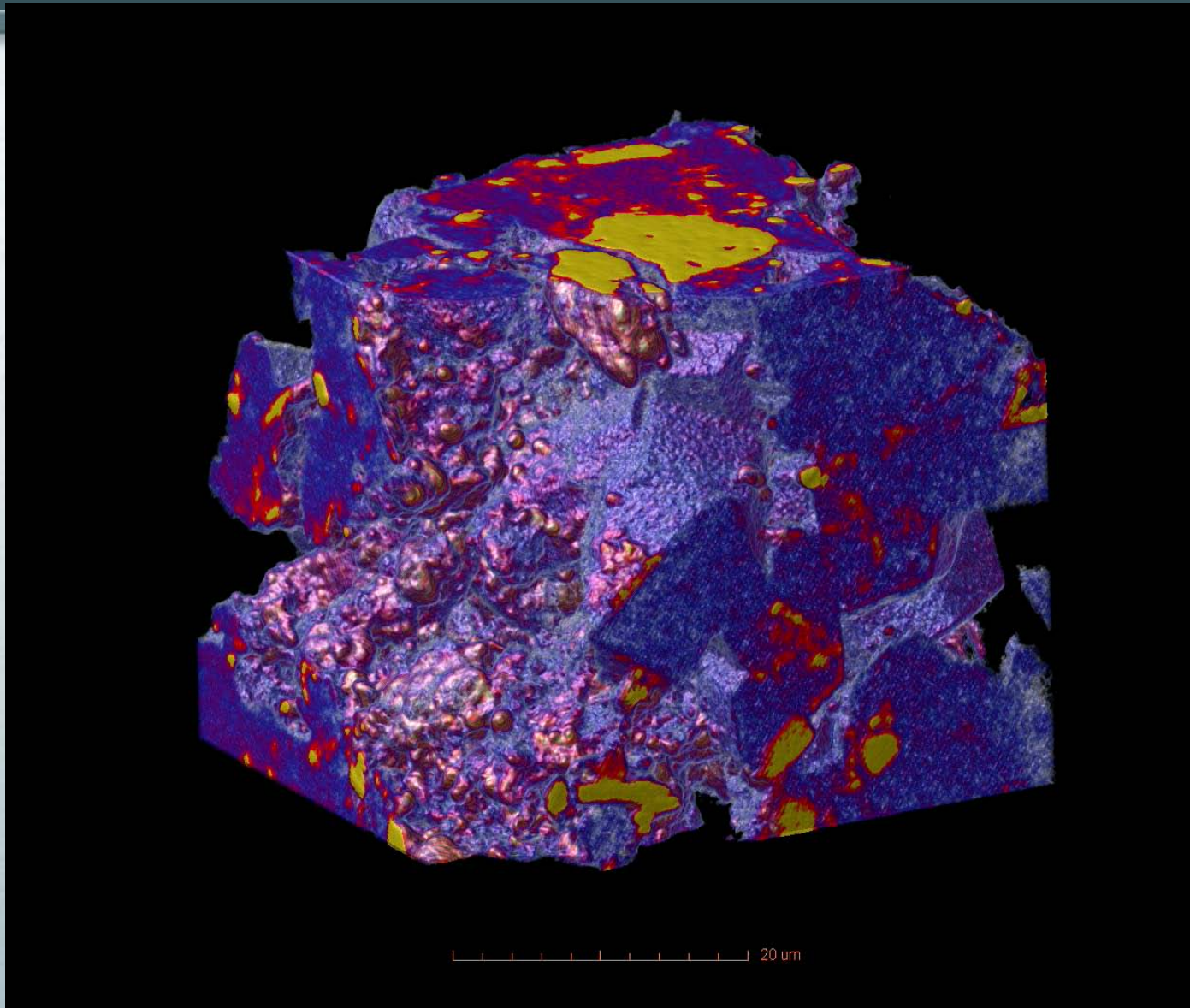
X-ray Tomography of Polymer Photonic Crystal 2D Slices



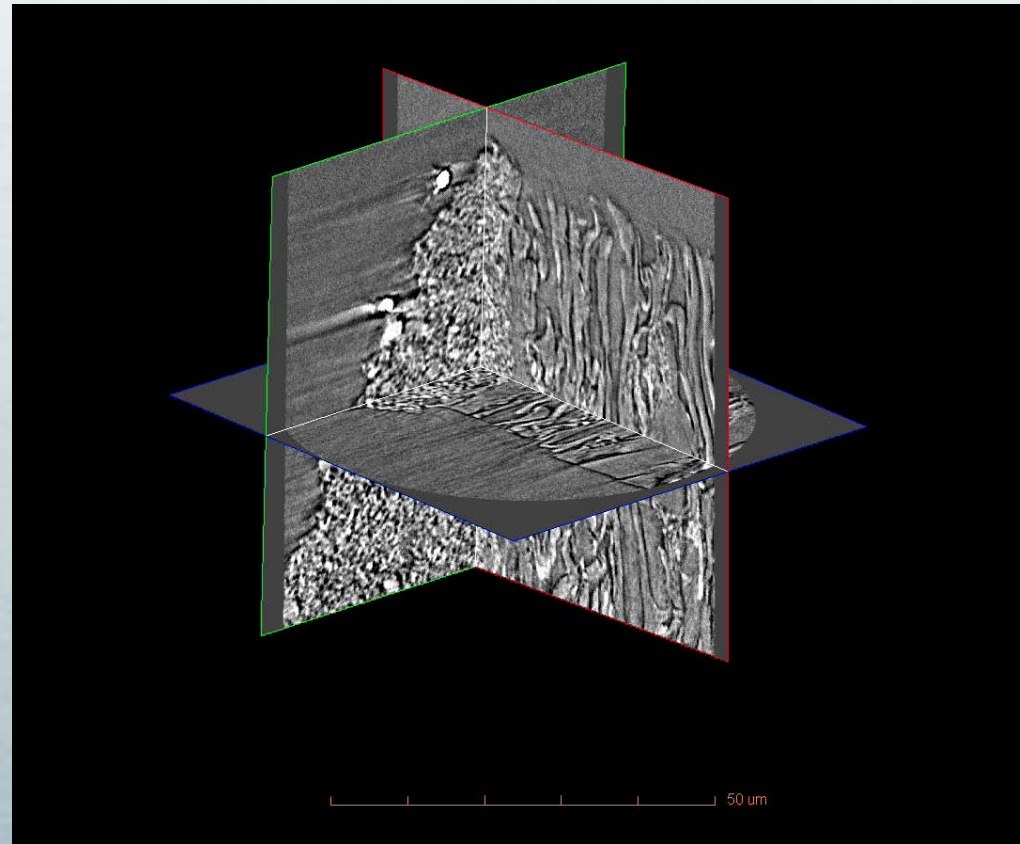
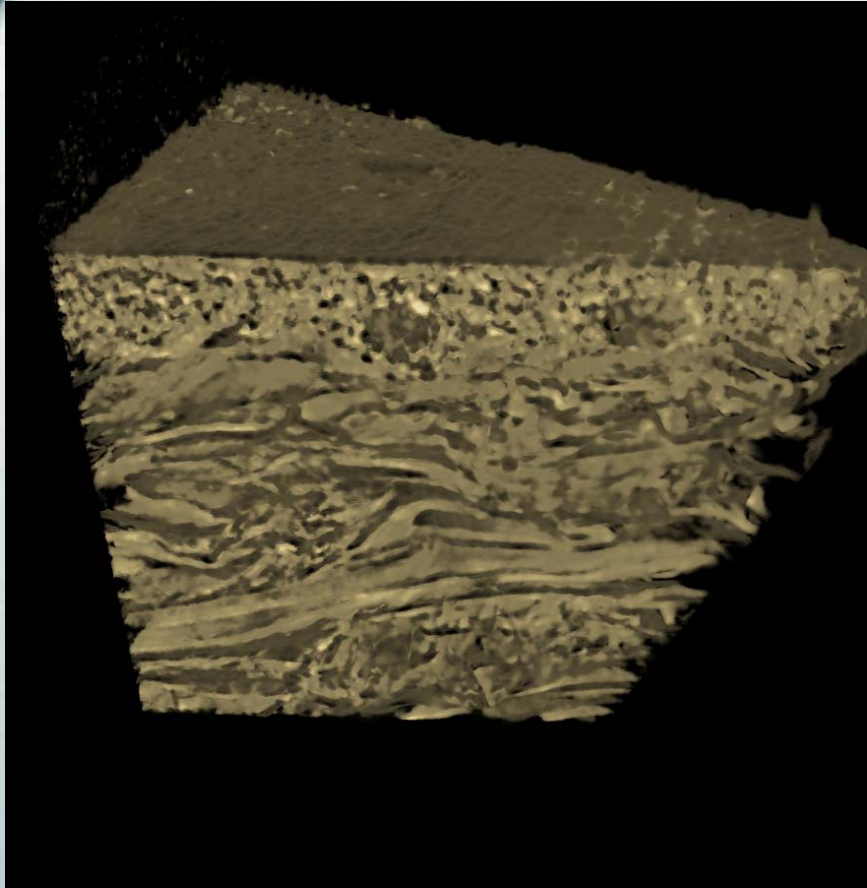
- 8 layers are observed in the crystal
- Air-polymer interfaces are clearly revealed

* See attachment for slice movies
16

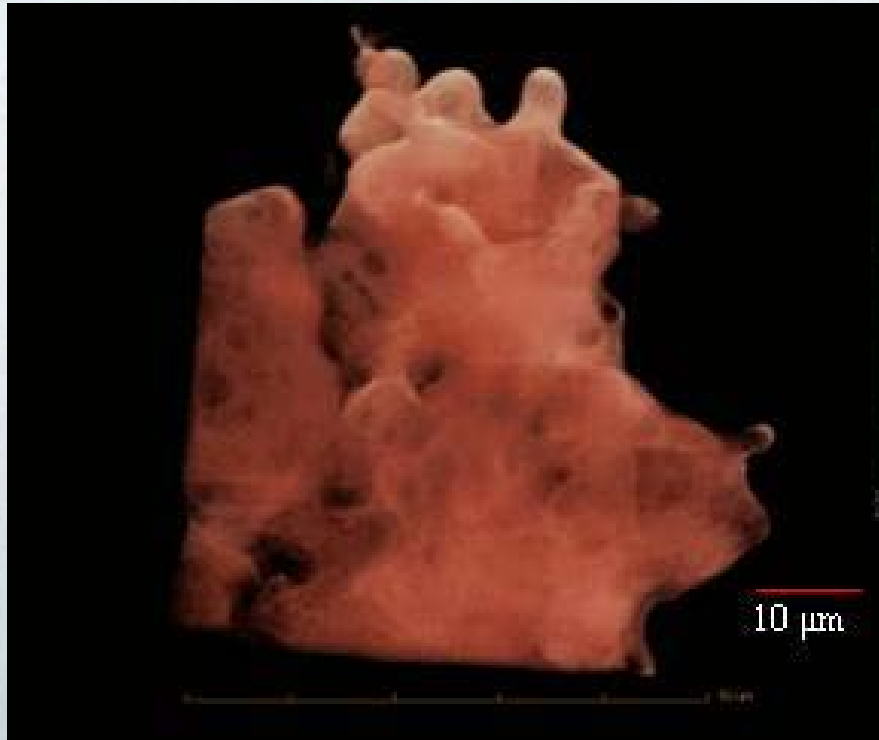
X-ray Tomography of an Alumina Particle



X-ray Tomography of Paper

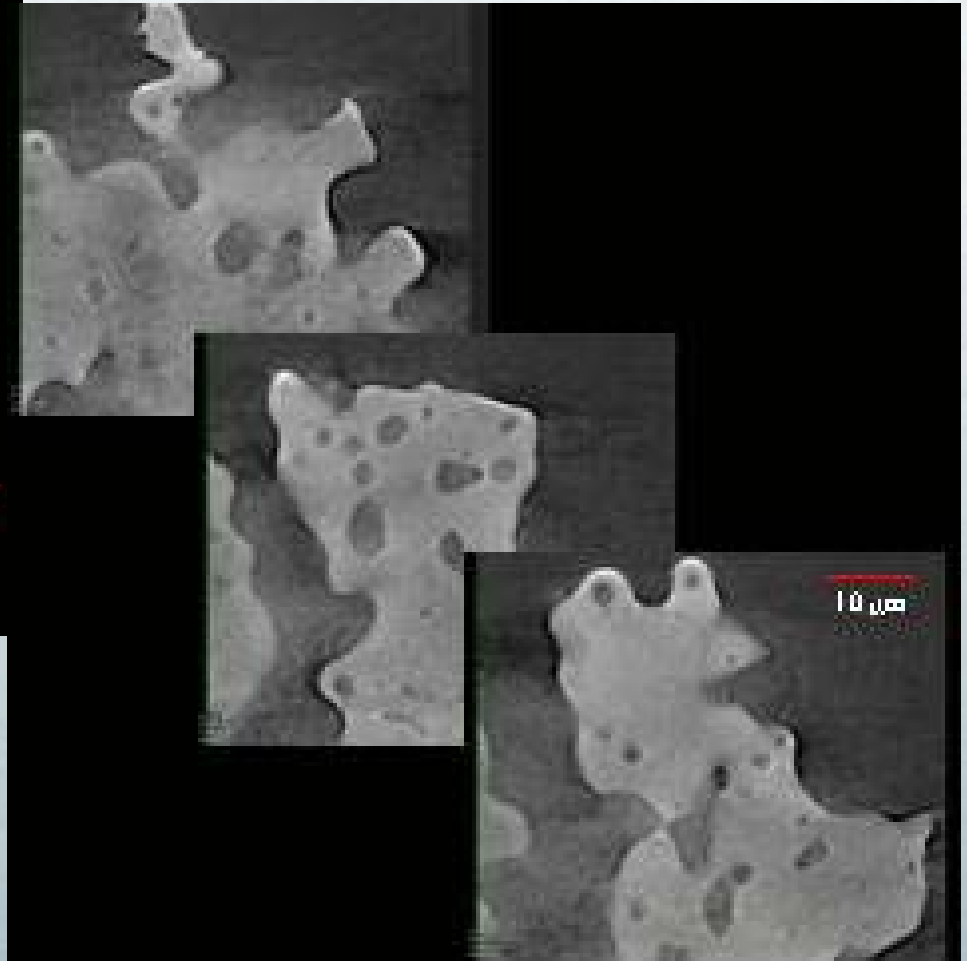


3D Imaging of Titanium Oxide Foam at 150 nm Resolution

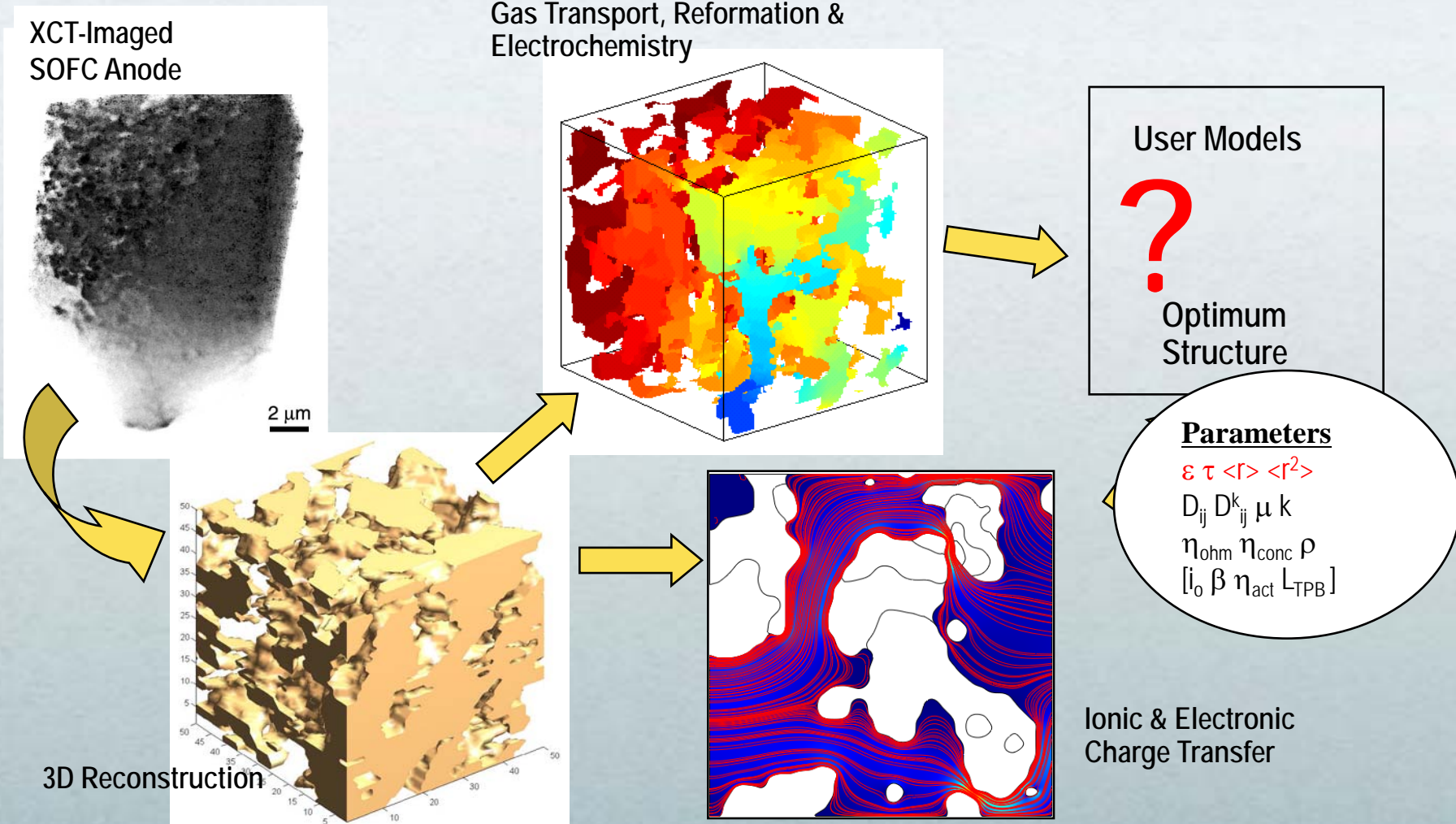


3D Rendered Image

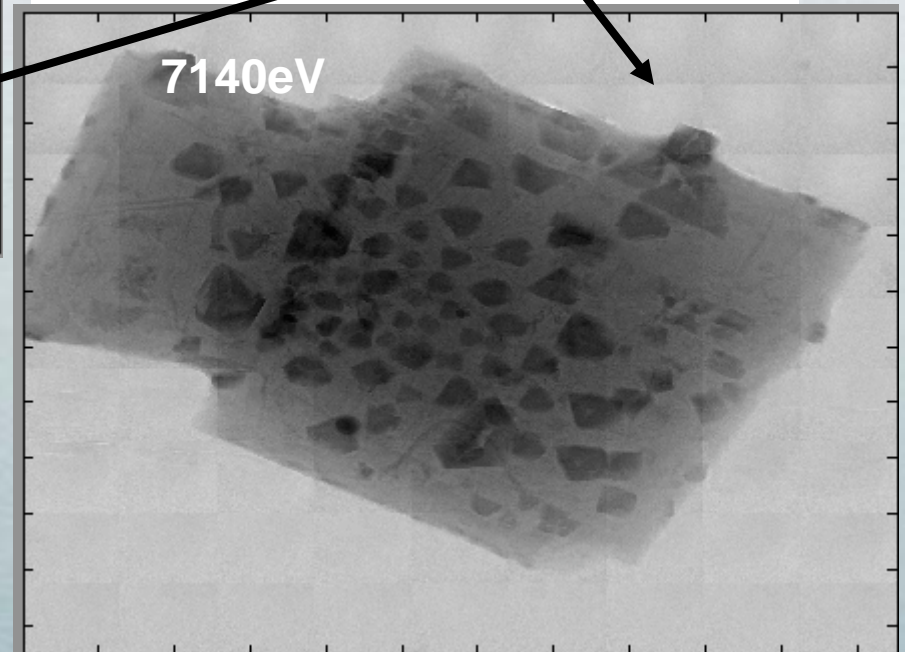
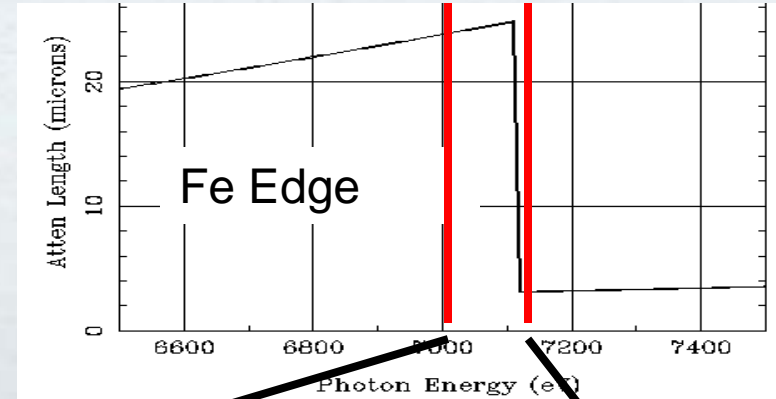
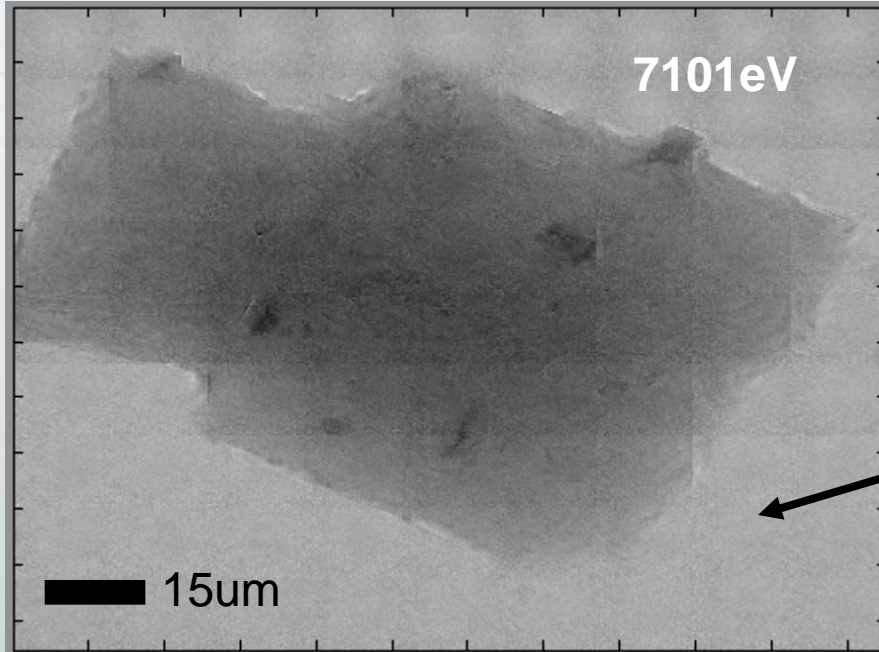
Virtual Cross Sections



Putting It All Together



Spectroscopic X-ray Imaging and Tomography: Meteorite

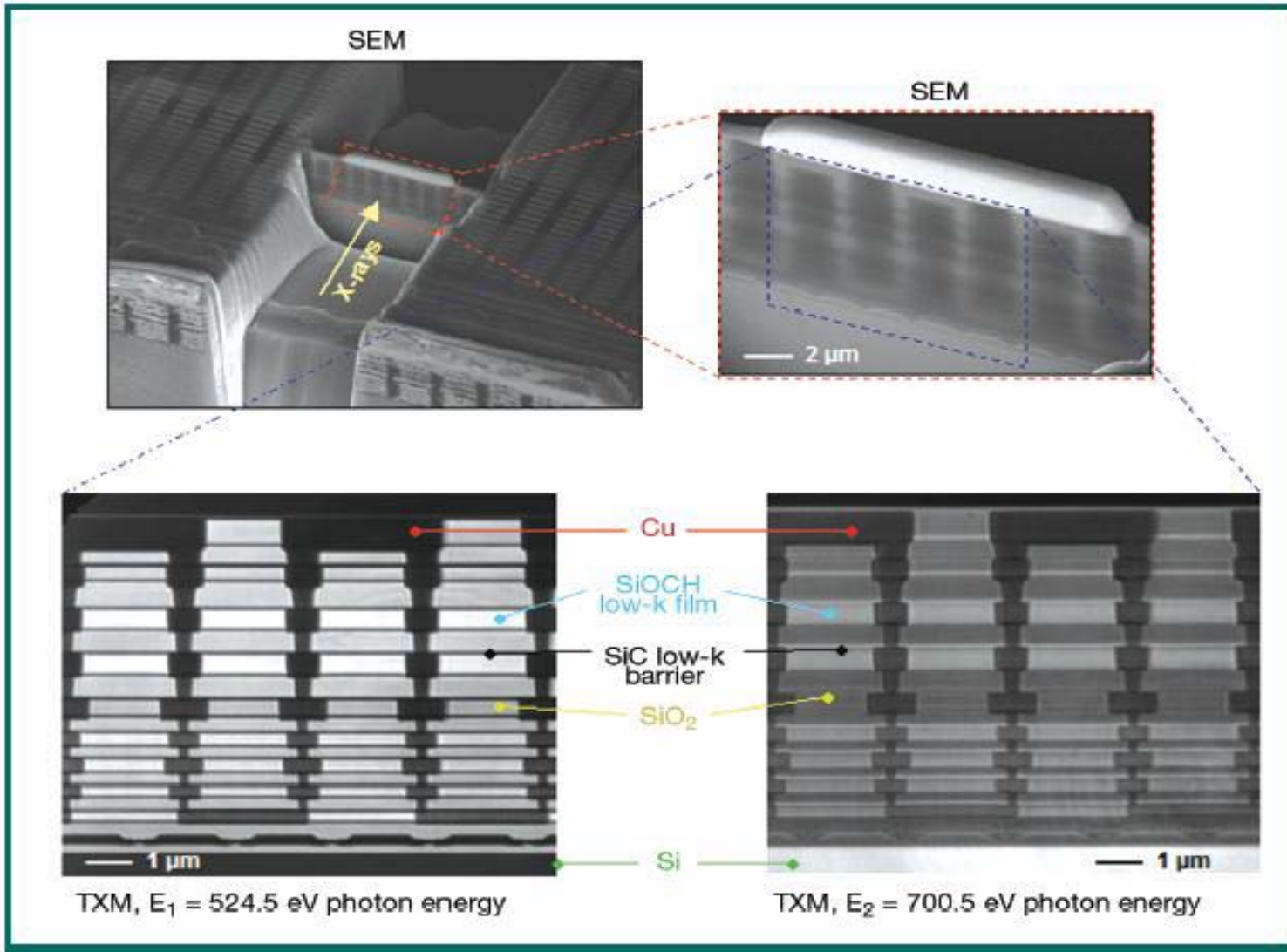


Identification of Fe-phases inside the Silicate matrix

Xradia nanoXCT-S100 at Stanford
Synchrotron Radiation Center, SLAC, USA

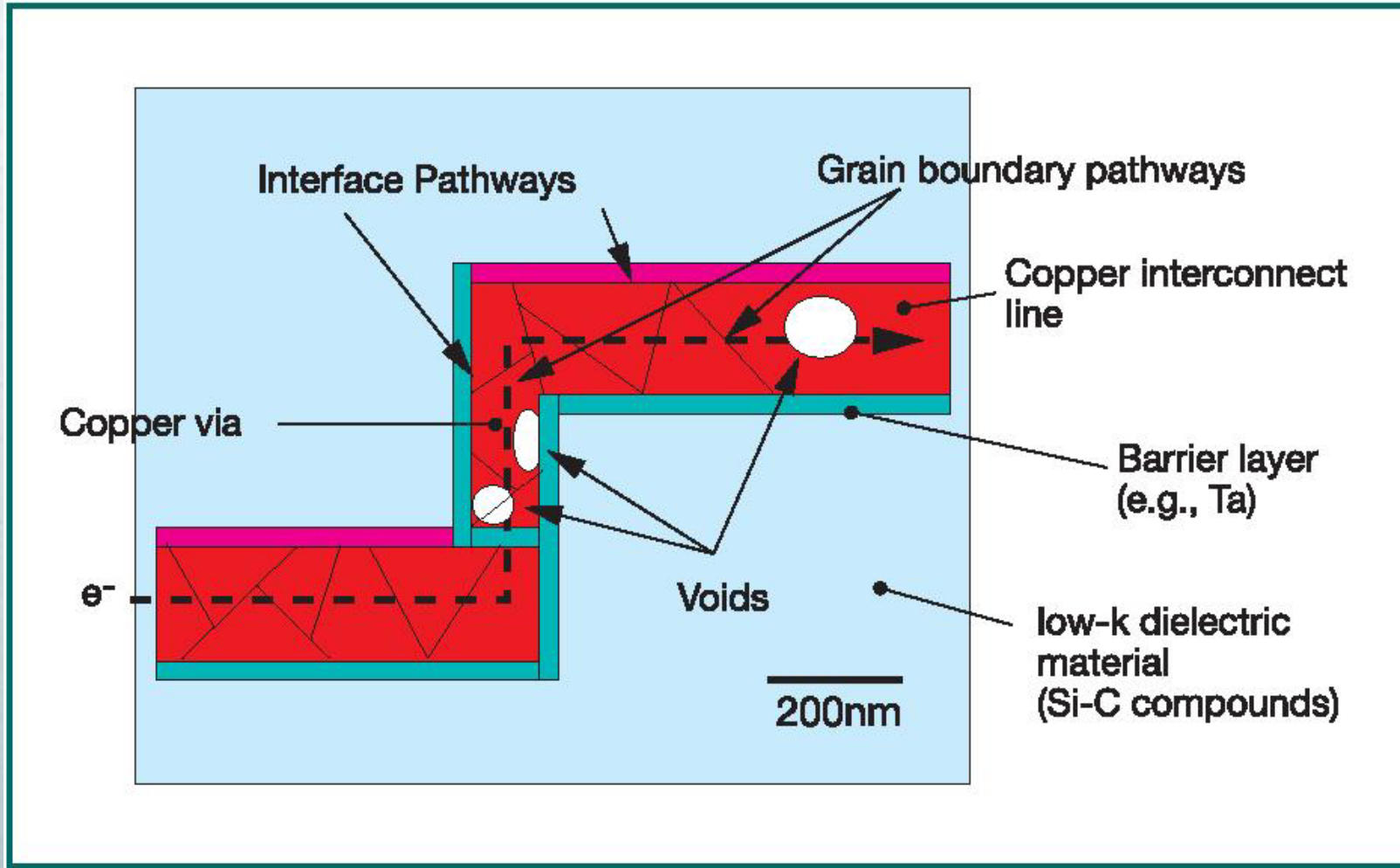
Data courtesy of P. Pianetta, S. Brennan
SSRL Xradia nanoXCT, unpublished

Some published TXM data from Synchrotron : Cu-low k



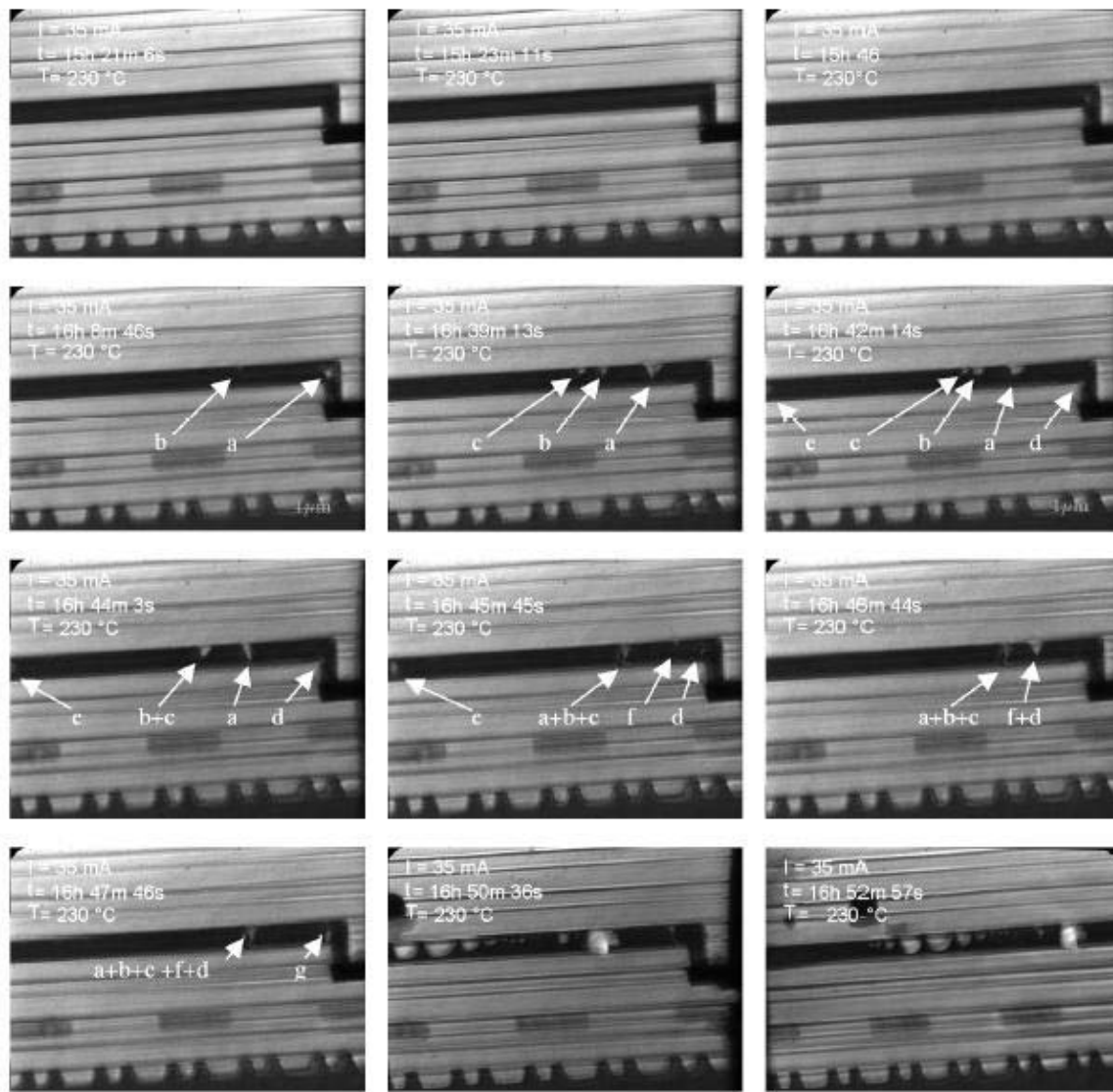
**High
Resolution
& High
Contrast**

Application : Electromigration- insitu



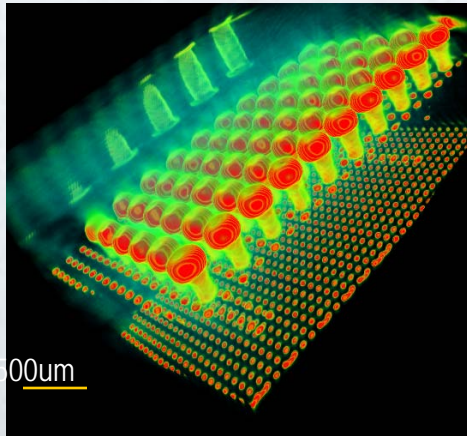
Cu via line test segment

Application : Electromigration- insitu

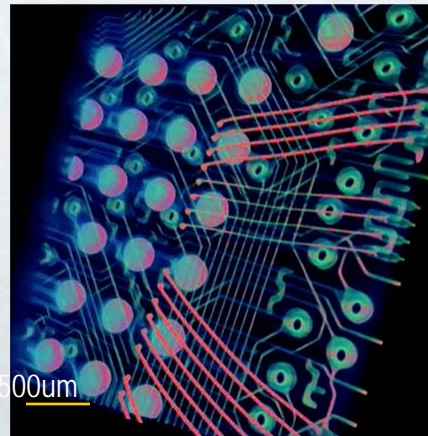


Selected Imaging Applications for IC Packaging (MicroXCT)

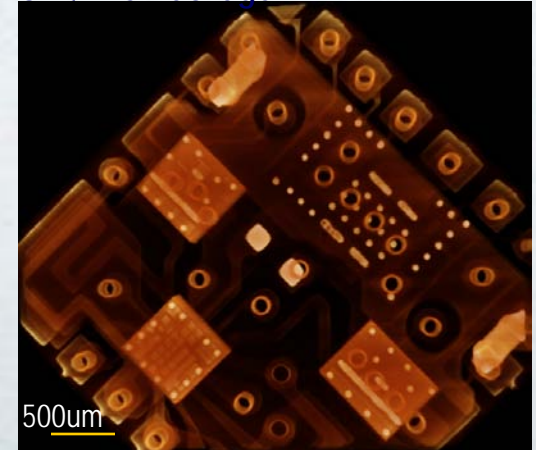
C4 Bump on Flip-chip



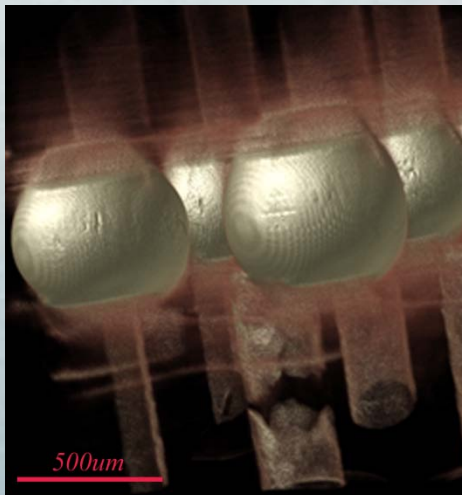
Wire bond packaging



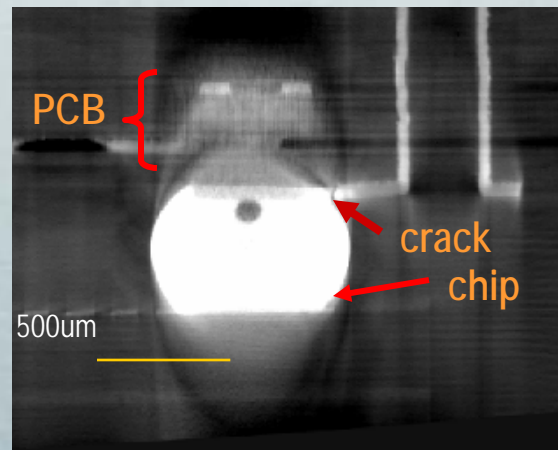
GaAs III/V IC Package



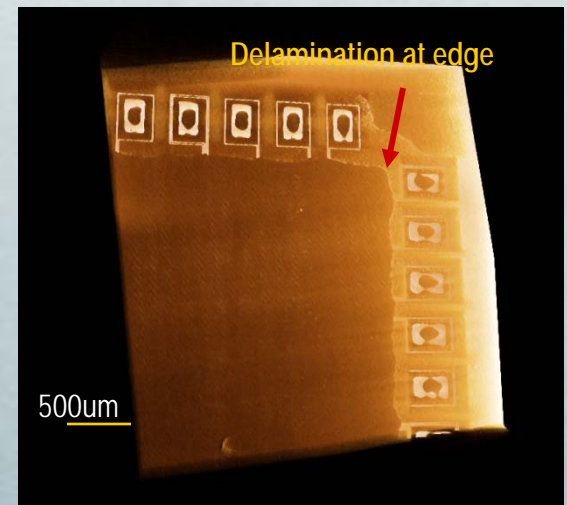
Solder Balls and Via Crack



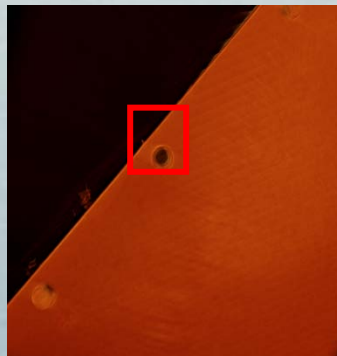
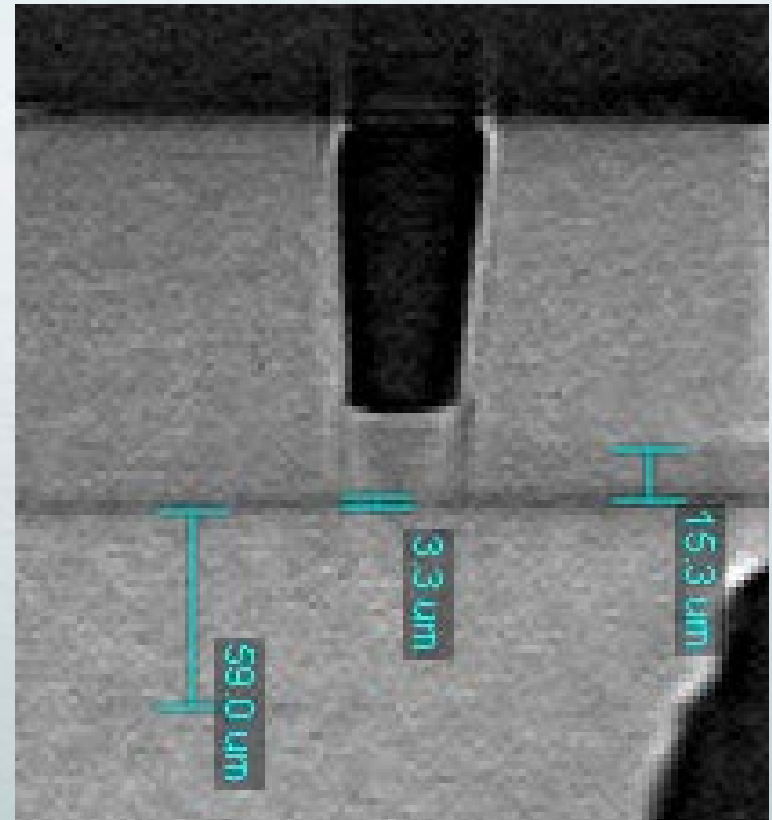
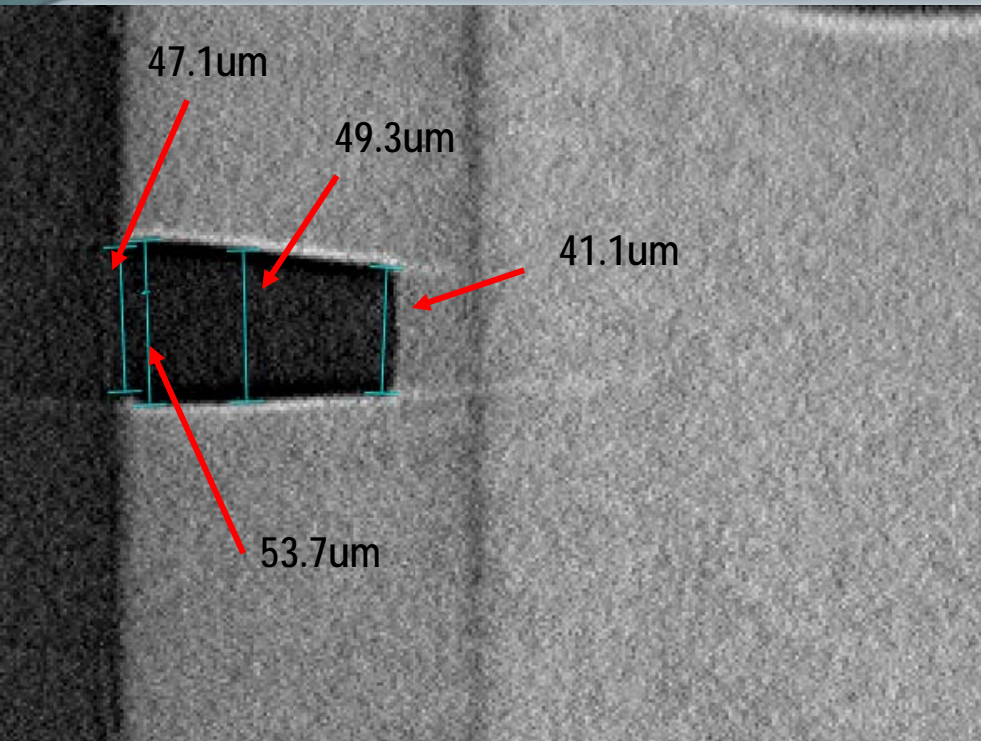
Solder Balls and Via Joint Crack



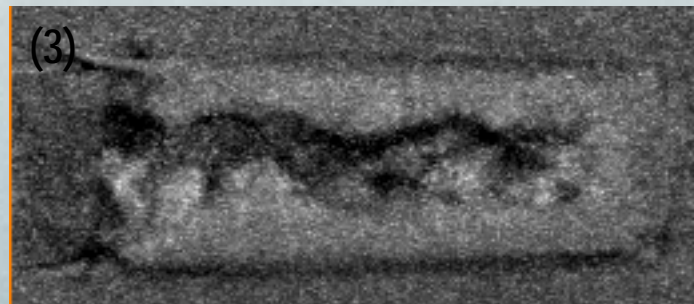
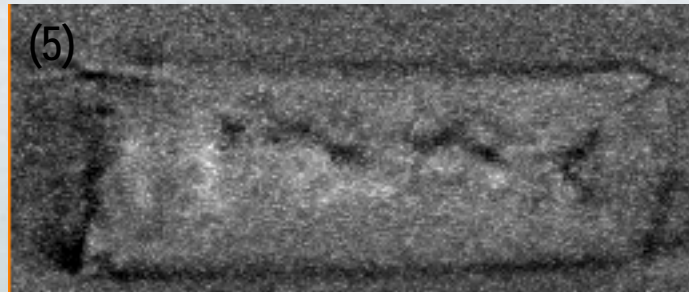
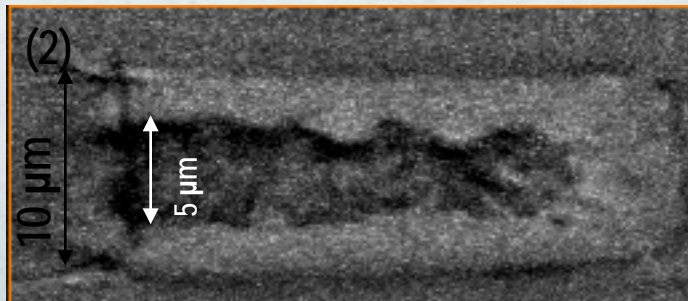
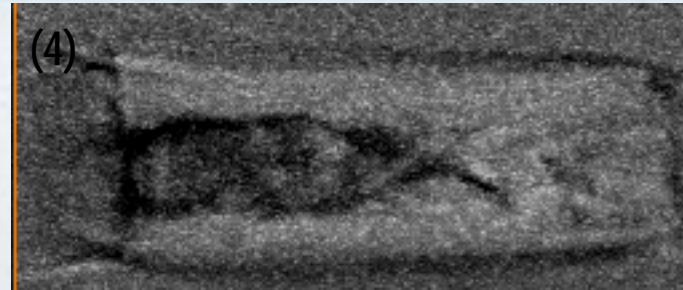
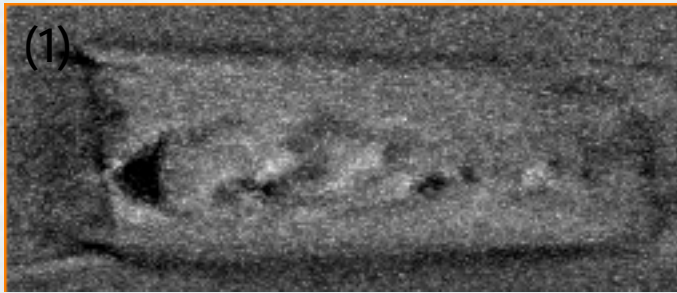
Delamination on Thin Die



Etched Through Si Via on glass carrier imaged at 1 um resolution with MicroXCT

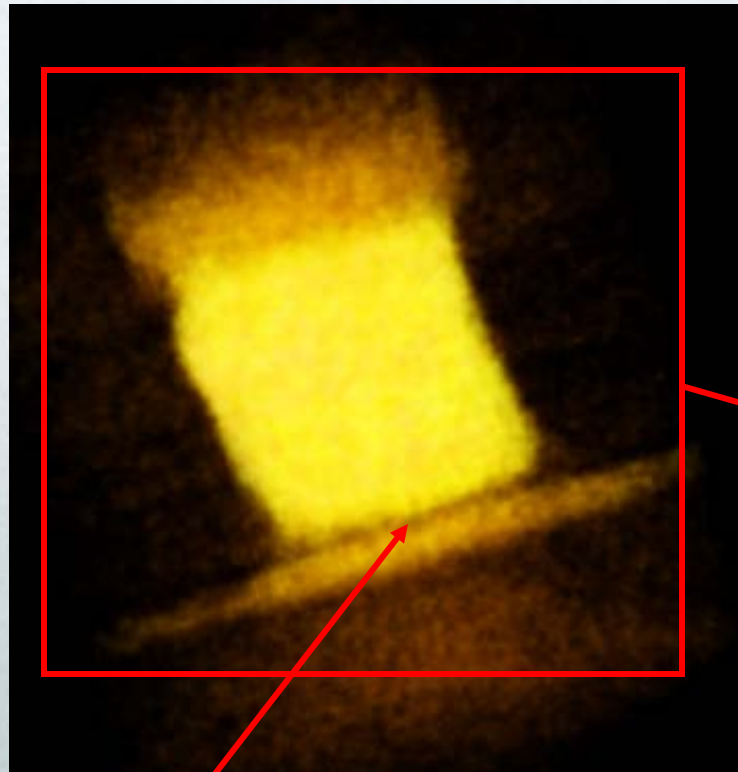


Non invasive void characterization: CT slices at 50 nm



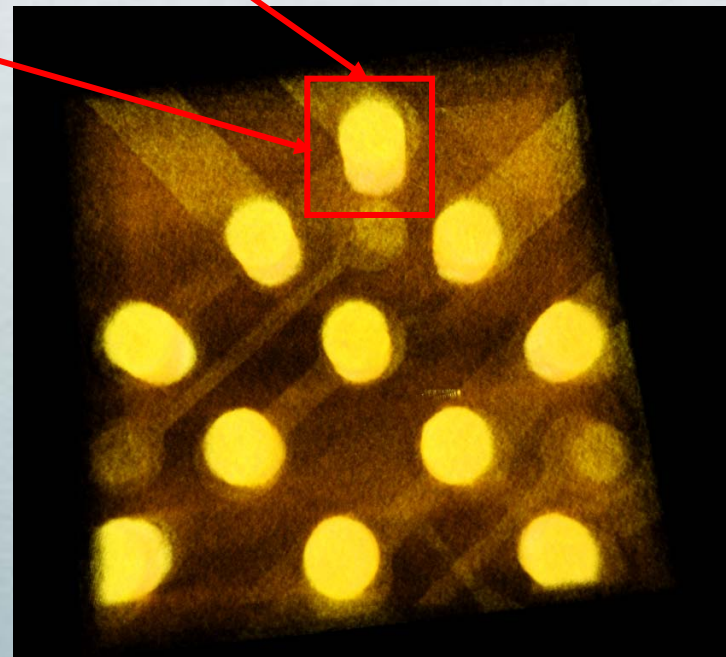
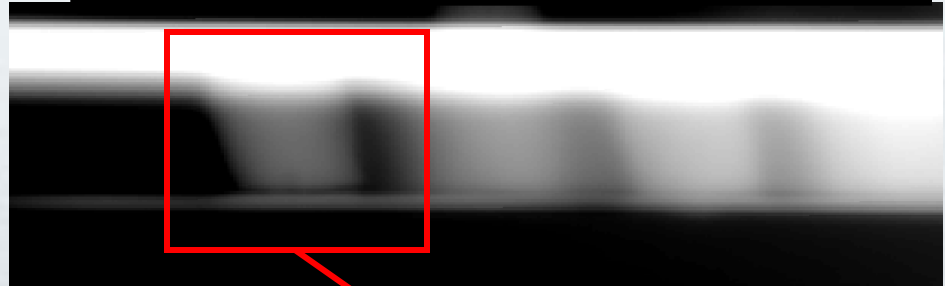
Virtual slices from a 10 μm via. The via has a ~ 5 μm void in the center

1. Solder non wet



*Complete non wet
taken from entire tomography*

Cracked ball taken from 20s scan, limited angle



Conclusions

- ❑ X-ray nondestructive 3D imaging with 30nm resolution has been developed for Cu interconnect characterization
- ❑ X-ray nondestructive 3D imaging offers good capability for TSV development and FA applications
- ❑ Time lapse imaging using x-rays can be used to study reliability issues